



Session Title:	[TuA2] Challenges and Opportunities in CMP
Session Date:	November 12 (Tue.), 2024
Session Time:	14:55-16:35
Session Room:	Room A (Capri Room, 2F, Paradise Hotel Busan)
Session Chair:	Prof. Keon-Soo Jang (Univ. of Suwon, Korea)

[TuA2-1] [Invited]

14:55-15:25

Planarization for Advanced Semiconductor Processing: Challenges and Opportunities

Hyo-Chol Koo and Jiho Kang (SK hynix Inc., Korea)

[TuA2-2] [Invited]

15:25-15:55

Eco-Innovations in Semiconductor Manufacturing: Sustainable CMP Approaches for the Next Generation

Jihoon Seo (Clarkson Univ., USA)

[TuA2-3]

15:55-16:15

Monitoring of Slurry Components and Concentrations for CMP Process via Raman Spectroscopy

Eun Su Jung and Sung Gyu Pyo (Chung-Ang Univ., Korea)

[TuA2-4]

16:15-16:35

Sulfate Radical Oxidation for Enhancing Polishing-Rate for WC-Film Chemical Mechanical Planarization

Man-Hyup Han, Myung-Hoe Kim, Hyun-Sung Koh (Hanyang Univ., Korea), Jin-Hyung Park (ENF Tech. Inc., Korea), and Jae-Gun Park (Hanyang Univ., Korea)